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Information Disclosure
Statement By Applicant

Applicants:

Savas, et al

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U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
WOT	A	4,028,135	6/7/1977	Vig et al			
WOT	B	4,782,267	11/1/1988	Collins et al			
WOT	C	5,234,540	8/10/1993	Grant et al			
WOT	D	5,954,884	11/21/1999	Lawing et al			
WOT	E	6,015,503	1/18/2000	Butterbaugh et al			
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WOT	G	US 6,183,566 B1	2/6/2001	Lawing et al			
WOT	H	US 6,277,767 B1	8/21/2001	Shiramizu et al			

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	I							
	J							
	K							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
WOT	L	Torek et al; UV/Fluorine Etching of Native Silicon Oxides; 1992; Proceedings of the Second International Symposium on Cleaning Technology in Semiconductor Device Manufacturing; pp 80-86.
WOT	M	Ito et al; Wafer Purification by Photochemical Dry Cleaning; March 1989, Semiconductor World; pp120-123
WOT	N	Zhang et al; Large Area Photochemical Dry Etching of Polymide; 1993; Applied Surface Science; Vol 69; pp 299-304
WOT	O	Vig; Ultraviolet-Ozone Cleaning of Semiconductor Surfaces; January 1992; US Army Laboratory Command (LAPCOM) Technical Report
Examiner		Date Considered
Mameen Khan		03/02/2004

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.